Notice of Allowability	Application No.	Applicant(s)	
	10/627,228	MOGHADAM ET AL.	
	Examiner	Art Unit	
	Rodney G. McDonald	1795	
The MAILING DATE of this communication appeall claims being allowable, PROSECUTION ON THE MERITS IS nerewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RID of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this apport or other appropriate communication IGHTS. This application is subject to	olication. If not included will be mailed in due course. THIS	9
1. $igotimes$ This communication is responsive to <u>After Final Amendme</u>	nt filed 10-16-07.		
2. X The allowed claim(s) is/are <u>1-28</u> .			
<ul> <li>Acknowledgment is made of a claim for foreign priority unally all b) Some* c) None of the: <ol> <li>Certified copies of the priority documents have</li> <li>Certified copies of the priority documents have</li> <li>Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)).</li> </ol> </li> <li>* Certified copies not received:</li> </ul> <li>Applicant has THREE MONTHS FROM THE "MAILING DATE"</li>	e been received. e been received in Application No cuments have been received in this r	national stage application from the	
noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.  1.  A SUBSTITUTE OATH OR DECLARATION must be subm		S AMENDMENT or NOTICE OF	
INFORMAL PATENT APPLICATION (PTO-152) which give	es reason(s) why the oath or declara	tion is deficient.	
5. CORRECTED DRAWINGS (as "replacement sheets") mus	st be submitted.		
(a) ☐ including changes required by the Notice of Draftspers	·	948) attached	
1)  hereto or 2)  to Paper No./Mail Date			
(b) ☐ including changes required by the attached Examiner's Paper No./Mail Date			
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in t			
<ol> <li>DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT</li> </ol>			
Attachment(s)	5 <b></b> 10 10		
1. Notice of References Cited (PTO-892)	5. Notice of Informal P		
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6.		
3. Information Disclosure Statements (PTO/SB/08), Paper No./Mail Date	7.   Examiner's Amendn	nent/Comment	
4. ☐ Examiner's Comment Regarding Requirement for Deposit	8. X Examiner's Stateme	ent of Reasons for Allowance	
of Biological Material	9.	Hoshe, Showl	
		RODNEY G. MCDONALD PRIMARY EXAMINER	

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## **REASONS FOR ALLOWANCE**

The following is an examiner's statement of reasons for allowance:

Claims 1, 3-14, 16, 17 and 27 are allowable over the prior art of record because the prior art of record does not teach the claimed subject matter including converting the silicon- containing reactant into a silica glass insulating compound using primarily thermal energy to provide activation energy to drive the deposition reaction by exposing the substrate to oxygen radicals formed from a second reactant while biasing the substrate to promote a sputtering effect.

Claims 2, 19-22 and 28 are allowable over the prior art of record because the prior art of record does not teach the claimed subject matter including converting the silicon-containing reactant into a silica glass insulating compound by exposing the substrate to oxygen radicals formed from a second reactant while introducing a fluent gas into the chamber and biasing the substrate to promote a sputtering effect, wherein an average atomic mass of all atomic constituents introduced into the chamber during the converting step is less than or equal to an average atomic mass of oxygen

Claims 15-28 are allowable over the prior art of record because the prior art of record does not teach the claimed subject matter including converting the silicon-containing reactant into a silica glass insulating compound by exposing the substrate to a plasma formed from a second reactant comprising oxygen atoms while biasing the substrate to promote a sputtering effect, wherein an average atomic mass of all atomic constituents introduced into the chamber during the converting step is less than or equal to an average atomic mass of oxygen and wherein the substrate is maintained at a

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temperature between 300-800°C during growth of the silica glass film and wherein the silica glass film grows up from the bottom surface of the gap at a rate greater than it grows inward on the sidewall surface of the gap.

The closest prior art of record to Chiang et al. (U.S. Pat. 6,428,859) fails to suggest utilizing thermal energy to drive the reaction but instead uses kinetic energy. Furthermore, the combination of Chiang et al. (U.S. Pat. 6,428,859) with Sherman (U.S. Pat. 6,342,277) results in an oxygen source and one of the ion feed gases described in Chiang during the converting step having an average atomic mass greater than oxygen. The combination of Sherman and Chiang et al. does not result in the invention of claims 2 and 15 which requires that the average atomic mass of all constituents introduced into the chamber during the converting step be less than or equal to the average atomic mass of oxygen.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Rodney G. McDonald whose telephone number is 571-272-1340. The examiner can normally be reached on M-Th with every Friday off..

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nam X. Nguyen can be reached on 571-272-1342. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Rodney G. McDonald Primary Examiner Art Unit 1795

RM

October 17, 2007